

WILL ST. TOWN BY

AMENDMENT 7	Docket No. 3430-0175P			
Application No.	Filing Date	Examiner		Art Unit
10/028,433-Conf. #4398	December 28, 2001	T. V. Duong		2871

Applicant(s): Young-Sang BYUN et al.

Invention: METHOD OF FORMING A LIQUID CRYSTAL LAYER USING INK JET SYSTEM

MS AF Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Transmitted herewith is an amendment in the above-identified application.

The fee has been calculated and is transmitted as shown below.

		CLAIM	S AS AMENI	DED			
	Claims Remaining After Amendment	Highest Number Previously Paid	Number Extra Claims Present		Rate		
Total Claims	20	- 20 =	0	X	50.00	0.00	
Independent Claims	2	- 3 =	0	x	210.00	0.00	
Multiple Depend	lent Claims (ch	eck if applicabl	e)				
Other fee (pleas	e specify):						
TOTAL ADDIT	IONAL FEE FO	OR THIS AME	NDMENT:			0.00	
x Large Entity Small Entity							
x No additiona	al fee is require	d for this amer	ndment				
	ge Deposit Acc			n the a	mount of \$	·	
A check in the	ne amount of \$		is enclo	sed.			
Payment by	credit card. Fo	orm PTO-2038	is attached.				
X The Director	r is hereby auth d below. A dup					lo. <u>02-2448</u>	
x Credit a	ny overpaymer	nt.					
x Charge a	any additional fil	ing or applicatio	n processing t	ees re	guired under	37 CFR 1.16 and 1.17.	
Esther H. Chon Attorney Reg. N	tuc	ling				March 27, 2008	
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Docket No.: 3430-0175P

(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of: Young-Sang BYUN et al.

Application No.: 10/028,433

028,433 Confirmation No.: 4398

Filed: December 28, 2001

Art Unit: 2871

For: METHOD OF FORMING A LIQUID

CRYSTAL LAYER USING INK JET SYSTEM

Examiner: T. V. Duong

AMENDMENT AFTER FINAL OFFICE ACTION

MS AF Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

INTRODUCTORY COMMENTS

In response to the Examiner's Office Action dated December 27, 2007, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

This reply includes:

Amendments to the Claims; and

Remarks.